

CONTENTS

Regular paper

- The Dependence of the Lattice Parameters and the Metal Containing Network Positions on Temperature and Oxygen Content in BSCCO2223 High Tc Phase Superconductor** 1
 S. Tsunakawa, Y. Nikura, N. Iwata and M. Konno

Symposium of Domain-Structure-Related Properties and Advanced Materials

- Preface** 5
- Flux Growth of ⁵⁷Fe-enriched Very High Quality Iron Borate Single Crystal and Observation of Magnetic Domain Structure using X-ray Double Crystal Topography** 7
 Takaya Mitsui, Humihiko Takei, Shinji Kitao, Makoto Seto, Taikan Harami, Xiaowei Zhang, Yoshitaka Yoda and Seishi Kikuta
- Electronic Structure of Nd-doped Bi₄Ti₃O₁₂ Single Crystal Probed by Soft-X-Ray Emission Spectroscopy** 11
 Tohru Higuchi, Takashi Goto, Yuji Noguchi, Masaru Miyayama, Takeshi Hattori and Takeyo Tsukamoto
- Growth of Bi₄Ti_{3-x}Zr_xO₁₂ Single Crystal by Floating Zone Method** 15
 Tohru Higuchi, Yoshiyuki Moriuchi, Makoto Satake, Takeshi Hattori and Takeyo Tsukamoto
- Preparation of Pb(Zr,Ti)O₃ Thin Films with Graded Composition Profiles by RF-Sputtering** 19
 Kazuki Nakano, Takaaki Suzuki, Isaku Kanno, Hidetoshi Kotera and Kiyotaka Wasa
- Ferroelectric Properties of Ba₂NaNb₅O₁₅ Thin Films Prepared by Pulsed Laser Deposition** 23
 Tohru Higuchi, Naoaki Machida, Taro Yamasaki, Takayuki Kamei, Takeshi Hattori and Takeyo Tsukamoto
- Ferroelectricity and Electronic State of (Sr,Ba)Nb₂O₆ Thin Film Prepared on La-doped SrTiO₃ Substrate** 27
 Tohru Higuchi, Yoshiki Ebina, Takeshi Hattori and Takeyo Tsukamoto
- Electric Properties of Bi_{4-x}Pr_xTi₃O₁₂ Lead-Free Piezoelectric Thick Films with a-/b-Mixed Domain Configuration** 31
 Hirofumi Matsuda, Takashi Iijima and Itaru Honma
- Synthesis and Properties of Nd-substituted Bismuth Titanate Polycrystalline Thin Films with a-/b-axes Orientations** 35
 Masahiro Kurachi, Hirofumi Matsuda, Itaru Honma, Takashi Iijima, Hiroshi Uchida and Seiichiro Koda
- Preparation and Properties of Nd-Substituted Bi₄Ti₃O₁₂-SrBi₄Ti₄O₁₅ Thin Films by Chemical Solution Deposition** 39
 Keiichi Imada, Tetsuo Shimura, Wataru Sakamoto and Toshinobu Yogo
- Preparation and Characterization of (1-x)BiScO₃-xPbTiO₃ Thin Films through Metal-Organic Compounds** 43
 Hiroshi Yamazaki, Tetsuo Shimura, Wataru Sakamoto and Toshinobu Yogo
- Effects of Sample Geometry on Electric-Field-Induced Displacements in Pt/PZT/Pt/SiO₂/Si System Investigated by Finite Element Method** 47
 Hirotake Okino, Kazuo Nakamura, Hirofumi Matsuda, Takashi Iijima, Shintaro Yokoyama, Hiroshi Funakubo and Takashi Yamamoto
- X-ray Diffraction Topography on Ferroelectric Materials** 51
 Yasuhiro Yoneda, Yoshiki Kohmura, Yoshio Suzuki, Shin-ichi Hamazaki, Masaaki Takashige and Jun'ichiro Mizuki
- Domain Observation of Rare-earth-substituted Bismuth Titanate Single Crystals** 55
 Shinichi Katayama, Masayuki Soga, Yuji Noguchi and Masaru Miyayama

Dependence of the Domain Structures of PMN-xPT Single Crystals on Cooling Rates across the Relaxor-Ferroelectric Phase Transition	59
Junichi Sakamoto, Hirotake Okino and Takashi Yamamoto	
Growth, Structure and Piezoelectric Properties of Ln₃Ga₅SiO₁₄ (Ln= La, Nd) Single Crystals	63
Hiroaki Takeda, Shintaro Izukawa, Hiroyuki Shimizu, Takashi Nishida, Soichiro Okamura and Tadashi Shiosaki	
Size and Temperature Induced Phase Transition Behaviors of Barium Titanate Nanoparticles	67
Takuya Hoshina, Hirofumi Kakemoto, Takaaki Tsurumi, Satoshi Wada and Masatomo Yashima	
Ferroelectric Domain Architecture for Novel Devices	71
Kazuya Terabe, Xiaoyan Liu, Xijun Li and Kenji Kitamura	
Real-Space Observation of Ferroelectric Domains in Organic Charge-Transfer Complexes by Electromodulation Method	75
Hideo Kishida, Ken Fujinuma, Hisashi Takamatsu and Hiroshi Okamoto	
Enhanced Piezoelectric Properties of Lead-free Piezoelectric Materials by Domain Engineering	79
Satoshi Wada, Koichi Yako, Hirofumi Kakemoto and Takaaki Tsurumi	
Impedance Response Analysis of Domain Structures in Pb[(Zn_{1/3}Nb_{2/3})_{0.91}Ti_{0.09}]O₃ Single Crystal with Giant k₃₁	83
Toshio Ogawa	
Bi₂MoO₆-Based Natural-Superlattice of Bismuth-Layer-Structured Ferroelectric Thin Films	87
Akira Shibuya, Minoru Noda, Masanori Okuyama and Keisuke Saito	
Control of Shape and In-plane Orientation of Self-Assembled PbTiO₃ Nanoislands Prepared by MOCVD	93
Hajime Nonomura, Masaki Nagata, Hironori Fujisawa, Masaru Shimizu, Hirohiko Niu and Koichiro Honda	
Investigation of Annealing Programs by Hot Isostatic Pressing for Crystallization of Amorphous Pb(Zr_{0.3}Ti_{0.7})O₃ Thin Films	97
Koji Fukushima, Masafumi Kobune, Yusuke Nishioka, Toru Yamaji, Tetsuo Yazawa, Hironori Fujisawa and Masaru Shimizu	
Charge Ordered Microdomains in Cr Doped AlV₂O₄	101
K. Kurushima, Y. Horibe, S. Mori, T. Asada, Y. Koyama, M. Shingu and T. Katsufuji	
Ultrasonic Transducers Composed of Functionally Gradient Piezoelectric Ceramics	105
Sadayuki Takahashi, Shohei Fukuda and Noboru Ichinose	
Giant Polarization Properties of Ba-based Bismuth Layer-Structured Ferroelectrics with Superlattice-structure	111
Tomo Kobayashi, Yuji Noguchi and Masasu Miyayama	
<i>Symposium of Fabrication, Characterization and Applications of Organic Ultrathin Films</i>	
Preface	115
Grazing Incidence X-ray Diffraction of Merocyanine J-Aggregate Monolayers at the Air-Water Interface	117
Noritaka Kato, Kazuya Yuasa, Takeshi Araki, Yoshiaki Uesu, Ichiro Hirosawa, Masugu Sato, Naoshi Ikeda and Ken-ichi Iimura	
Light-Induced J-aggregation in Langmuir and Langmuir-Blodgett Films	123
Mutsuyoshi Matsumoto	
Alignment Control of Organic Thin Films by Recrystallization under Laser Heating	127
K. Nakayama, K. Iida, J. Tokuhira, K. Saitoh, S. Shichijyo and H. Yanagi	
Structural and Transport Studies of BEDO-TTF-Arachidic-Acid Conducting Langmuir-Blodgett Films	131
H. Ito, H. Tamura, S. Kuroda, H. Yamochi	

Infrared Spectroscopic Study on LB Films Based on Ditetradecyldimethylammonium-Au(dmit)₂ Salt	135
Ryo Watanabe, Shin-ichi Morita, Yasuhiro F. Miura and Michio Sugi	
Electron Transfer Reactions of Electronics Molecules Embedded in Cationic Lipid Thin Films	139
Takashi Nakanishi, Katsuhiko Ariga, Karl M. Kadish and Naotoshi Nakashima	
Crystal Structure and Formation of Organized Molecular Films of Fluorinated Comb Copolymers	143
Atsuhiko Fujimori, Ryosuke Masuya, Kouya Kumagai, Toru Masuko, Eisuke Ito, Masahiko Hara, Kaname Kanai, Yukio Ouchi and Kazuhiko Seki	
New Applications of the Least Squares Method in Spectroscopic Characterization of Thin Organic Films	147
Keiichi Ikegami	
LB Molecule Orientation by DC Electric Field between Line Electrodes	153
Sadao Uegusa, Akinori Endo, Tsutomu Miyasaka and Akinori Konno	
Nano-Structured Alignment of C₆₀	159
A. Kinjo, H. Sakamoto, H. Okuyama, N. Iwata and H. Yamamoto	
Aggregation Control and Photochemical Behaviors in UV-Sensitive Organosilane Monolayers Bearing Naphthylmethylsulfonyl Groups	163
Motohiro Tagaya, Masaru Nakagawa and Tomokazu Iyoda	
Chemical Reaction between an LB Film of an Organic Electron Donor and That of an Organic Acceptor	167
Keiichi Ikegami, Hitoshi Ohnuki, Mitsuru Izumi and Tatsuro Imakubo	
Absorption Spectrum of Phthalocyanine Derivatives LB Films	171
Kuori Katayama, Souki Yamaguchi, Takuya Hashimoto, Nobuyuki Iwata and Hiroshi Yamamoto	
Bright Luminescence from Organic EL Thin Films by Electron Beam Irradiation	175
Yasunori Hata, Tsuyoshi Ichinose, Nobuyuki Iwata and Hiroshi Yamamoto	
 <i>Symposium of Physics and Technology of Dielectric Thin Films for Future Electronic Devices</i>	
Preface	179
Suppression of Thermal Interface Degradation in High-k Film/Si by Helium	181
Kouichi Muraoka	
Photoemission Study on the Interfacial Reaction between Polycrystalline-Si Electrodes and HfO₂/Si Gate Insulators with <i>in-situ</i> Annealing	187
Haruhiko Takahashi, Satoshi Toyoda, Jun Okabayashi, Hiroshi Kumigashira, Masaharu Oshima, Yoshiharu Sugita, Guo Lin Liu, Ziyuan Liu and Koji Usuda	
The Role of Oxygen-related Defects on the Reliabilities of HfO₂-based High-k Gate Insulators	191
Kazuyoshi Torii, Kenji Shiraishi, Seiichi Miyazaki, Kikuo Yamabe, Mauro Boero, Toyohiro Chikyow, Keisaku Yamada, Hiroshi Kitajima, and Tunetoshi Arikado	
Analysis of Leakage Current through Al/HfAlO_x/SiON_x/Si(100) MOS Capacitors	197
S. Nagamachi, A. Ohta, F. Takeno, H. Nakagawa, H. Murakami, S. Miyazaki, T. Kawahara and K. Torii	
Transient Characteristics of HfAlO_x Gate Dielectric Films	201
Masakazu Goto, Keiichi Higuchi, Kazuyoshi Torii, Ryu Hasunuma and Kikuo Yamabe	
Electrical Characterization of HfAlO_x/SiON Dielectric Gate Capacitors	205
Y. Pei, S. Nagamachi, H. Murakami, S. Higashi, S. Miyazaki, T. Kawahara and K. Torii	
ECR Ar/O₂ Plasma Oxidation of HfN Thin Films for High Dielectric HfO_xN_y Formations	209
T. Kurose, T. Uchikawa, S. Ohmi and T. Sakai	
The Impact of Rapid Thermal Annealing on ALCVD-Al₂O₃/Si₃N₄/Si(100) Stack Structures - Photoelectron Spectroscopy	213
F. Takeno, A. Ohta, S. Miyazaki, K. Komeda, M. Horikawa and K. Koyama	

Low-Temperature Formation of Silicon Nitride Films using Nitrogen Plasma near Atmospheric Pressure	217
Ryoma Hayakawa, Takeshi Yoshimura, Mari Nakae, Tsuyoshi Uehara, Atsushi Ashida and Norifumi Fujimura	
Characterization of Amorphous Hafnium Silicate and Hafnium Aluminate Films by Grazing-Incidence X-ray Scattering	221
Ichiro Hirose, Hiroshi Kitajima and Kazuyoshi Torii	
Comparison of Reactivity of Exited Nitrogen Species Generated in RF Plasma and Atmospheric Pressure Plasma	225
Mari Nakae, Ryoma Hayakawa, Takeshi Yoshimura, Atsushi Ashida, Tsuyoshi Uehara and Norifumi Fujimura	
The Effect of the Annealing Process on Dielectric Properties of Ba(Ti,Zr)O₃ Thin Films Deposited by Sputtering	229
Mayumi Uno, Shuichi Murakami and Yoshiharu Kakehi	
Electrical Characterization of YMnO₃-based Metal-Ferroelectric-Insulator-Semiconductor Capacitor by Novel Method	233
Takeshi Yoshimura, Daisuke Ito, Kohei Haratake, Atsushi Ashida and Norifumi Fujimura	
Low-Temperature Growth of YMnO₃/Y₂O₃/Si Capacitor	237
K. Haratake, N. Shigemitsu, T. Yoshimura, A. Ashida and N. Fujimura	
Epitaxial Growth of ZnO Films on Ferroelectric YMnO₃ Films Deposited by the PLD Method	241
R. Arai, N. Shigemitsu, K. Masuko, T. Oshio, T. Yoshimura, A. Ashida and N. Fujimura	
Influence of Space Charge on the Dielectric Properties of ZnO:Mn Epitaxial Films	245
T. Oshio, K. Masuko, A. Ashida, T. Yoshimura and N. Fujimura	
Electrical Properties of Bi_{4-x}Pr_xTi₃O₁₂ (BPT) Thin Films Prepared by Sol-Gel Method	249
Tomoharu Aoki, Takeo Tani and Eisuke Tokumitsu	
Influence of the Preparation Process on Characteristics of Organic Electroluminescent Devices	253
Yuichiro Kikuchi and Shigetaka Fujita	
Photovoltaic Characteristics of Nitrogen-doped Camphoric Carbon Films Deposited by XeCl Excimer Laser	257
M. Rusop, S. M. Mominuzzaman, T. Soga, T. Jimbo and M. Umeno	
X-ray Photoelectron Spectroscopy Analysis on the Bonding Properties of Amorphous Carbon Nitride Films	261
M. Rusop, T. Soga and T. Jimbo	
 <i>Symposium of Frontier of Advanced Plasma Technology for Nano-Materials</i>	
Preface	265
Preparation of High-Quality a-Si:H using Cluster-Suppressed Plasma CVD Method and Its Prospects	267
Yukio Watanabe, Masaharu Shiratani and Kazunori Koga	
Formation of Atmospheric Pressure Plasma by Mesh Electrodes and My Desire for its Development	273
Satiko Okazaki	
High-Rate Growth of Highly-Crystallized Si Films from VHF Inductively-Coupled Plasma CVD	279
Nihan Kosku and Seiichi Miyazaki	
Fabrication of Polycrystalline Si Thin Film Transistor using Plasma Jet Crystallization Technique	283
Hirotaka Kaku, Seiichirou Higashi, Seiichi Miyazaki, Masahiko Asami, Hajime Watakabe, Nobuyuki Andoh and Toshiyuki Sameshima	

Fabrication of Diamond Nano-whiskers by Reactive Ion Etching	287
Chao Yang Li, Yusuke Aoki, Hiroaki Yoshimura and Akimitsu Hatta	
Measurement of Absolute Cu Atom Density in Magnetron Sputtering Plasmas	291
Junsi Gao, Nayan Nafarizal, Koichi Sasaki, Hiroataka Toyoda, Satoshi Iwata, Takeshi Kato, Shigeru Tsunashima and Hideo Sugai	
Production of Atmospheric Pressure Glow Discharge Using Semiconductor Opening Switch Diode	295
Koichi Takaki, Masato Hosokawa, Seiji Mukaigawa and Tamiya Fujiwara	
Absolute Densities of Ti Atoms and Ti⁺ Ions in Magnetron Sputtering Plasmas Measured by Laser-Induced Fluorescence	299
Nayan Nafarizal, Noriharu Takada, Keiji Nakamura, Tatsuhiko Yoshida and Koichi Sasaki	
Formation of Amorphous-CN Thin Films by the Deposition of CN Radicals – Absolute Density of Gas-phase CN	303
Haruhiko Ito and Hidetoshi Saitoh	
Production of Crystalline Si Nano-Particles Using VHF Discharges and Their Properties	307
Masaharu Shiratani, Tomohide Kakeya, Kazunori Koga, Yukio Watanabe and Michio Kondo	
Estimations of Plasma Parameters and Bias-Sputtering of Cu Films in Gas-Flow-Sputtering Operating at 1-Torr Pressure Region	311
Yoshifumi Saitou, Hiroshi Sakuma and Kiyoshi Ishii	
Plasma Treatment of Carbon Nano-powder Using RF Dielectric Barrier Discharge at Atmospheric Pressure	315
Akimitsu Hatta and Yusuke Aoki	
Evidence of Radical-free Etching of SiO₂ by Fluorocarbon Molecule under Ion Bombardment	319
Noriharu Takada, Hiroataka Toyoda and Hideo Sugai	